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**PATENT
30205/39513**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Young Sun Hwang et al.

Serial No.: 10/719,083

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For: Methods for Forming Fine
Photoresist Patterns

Group Art Unit: 1765

Examiner: Patricia Ann George

Confirmation No. 2261

) I hereby certify that this paper and the
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) P.O. Box 1450, Alexandria, Virginia
) 22313-1450

Michael R. Hull
Reg. No. 35,902
Attorney for Applicant

RESPONSE TO RESTRICTION REQUIREMENT AND AMENDMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Commissioner:

In response to the restriction requirement imposed in the office action mailed on July 6, 2005, applicants elect Group I, claims 1-9, without traverse and submit the following amendment to clarify the claimed invention.

Amendments to the specification appear on page 2 of this paper.

Amendments to the claims and a complete listing of the claims begins on page 3 of this paper.

Remarks appear on page 4 of this paper.